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Application Number	10/753,071
Filing Date	January 8, 2004
First Named Inventor	Tadashi NARITA
Art Unit	774 1713
Examiner Name	Unassigned H. H. H.
Attorney Docket Number	038788.53145US

U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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FOREIGN PATENT DOCUMENTS

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H. H. H.	AA	THEODORE. H. FEDYNISHYN, ET AL., "Fluoroaromatic Resists for 157-nm Lithography", Journal of Polymer Science and Technology, 2002, pp. 655-666, Volume 15, No. 4, Lexington, MA	
H. H. H.		RALPH R. DAMMEL ET AL., "New Resin Systems for 157 nm Lithography", Journal of Polymer Science and Technology, 2001, pp. 603-612, Volume 14, No. 4	

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